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Jiangyin Maideli Advanced Materials Co.,Ltd



maideli

■ About Us

Maideli Advanced Materials is a high-tech enterprise who professionally engaged in R&D ,production ,Sales and service of Sputtering Target ,Evaporation Materials ,Wafers, Quartz and Ceramic Products .

Maideli has been focus on the service of market in optic, optical communication ,panel display ,solar panel,TP,IC,LED chips ,decorative coating ,tooling coating ,low emission glass and so on .

As always , Maideli starts with what the customer required and with Satisfied end . The company continue to strengthen technological innovation ,strengthen production management ,accelerate the implementation of the technology and quality of the enterprise policy ,to provide better ,more detailed ,faster service to customers .

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SPUTTERING TARGET AND EVAPORATION MATERIALS



Oxides

Sulfides

Fluorides

Tellurides

Selenides

Borides

Carbides

Nitrides

Compounds



Cr Sputtering Target

Manufacturing Process : Hot Isostatic Pressing

Specification :Length:≤4000mm,OD:≤300mm.

Or as customers' requirements .

Relative Density >99.0%

Purity : 99.5% ~99.8%

Grain Size <50 μm

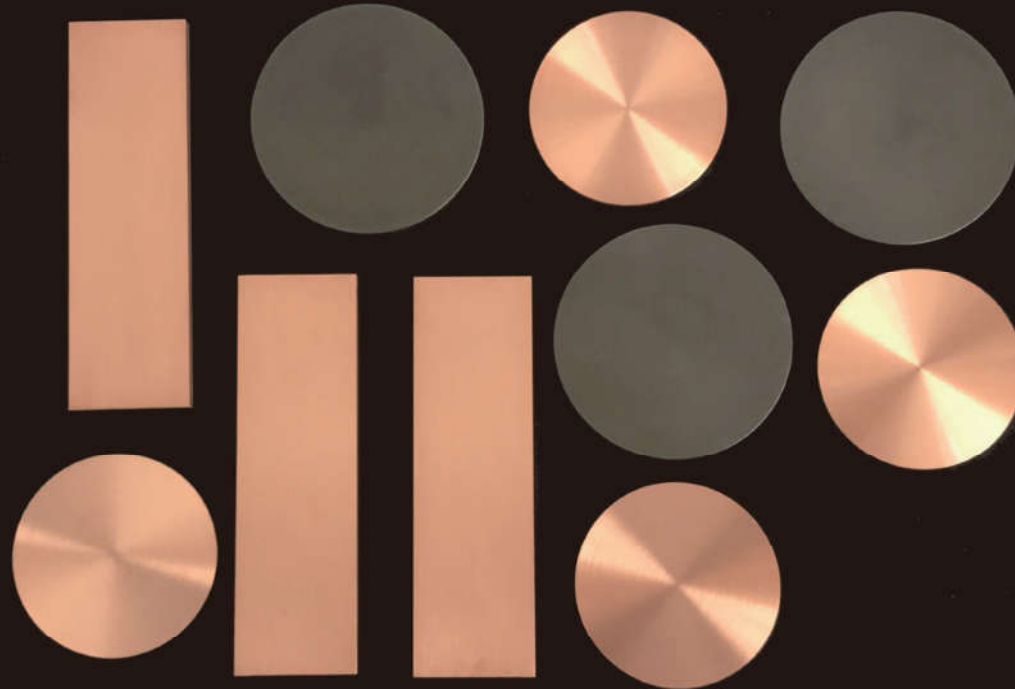
Ti Sputtering Target

Manufacturing Process : Vacuum melting technology

Specification :Max4000mm*300mm;Or as customers' requirements .

Purity : 99.7% ~99.999%





Al Sputtering Target

Manufacturing Process : Vacuum melting technology

Specification :Max4000mm*300mm;Or as customers' requirements .

Purity :99.99% ~99.999%z

Cu Sputtering Target

Manufacturing Process : Vacuum melting technology

Specification :Max4000mm*300mm;Or as customers' requirements .

Purity : 99.99% ~99.999%

Formula	Purity	Formula	Purity	Formula	Purity
Ag ₂ O	99.90%	BaTiO ₃	99.90%	CoFe ₂ O ₄	99.90%
Al/B	99.90%	Bi	99.99%	CoFeB	99.90%
Al/Cr	99.95%	Bi ₂ O ₃	99.99%	CoO Co ₃ O ₄	99.90%
Al/Cu	99.99% 99.999%	Bi ₂ Se ₃	99.99% 99.999%	Cr	99.5% 99.95%
Al/Mg	99.95%	BiTeSe	99.99% 99.999%	Cr ₂ O ₃	99.90%
Al/Si	99.99%	Bi ₂ Te ₃	99.99% 99.999%	Cr ₃ C ₂	99.90%
Al/Ti	99.90%	BiFeO ₃	99.90%	CrB ₂	99.5% 99.95%
Al/Zr	99.90%	Ca ⁵ (PO ₄) ₃ (O H)	99.90%	CrGe	99.95%
AlN	99.50%	CaF ₂	99.99%	CrN	99.50%
As ₂ Se ₃	99.99% 99.999%	CaO	99.90%	CrSi	99.95%
As ₂ Te ₃	99.99% 99.999%	Cd ₂ SnO ₄	99.90%	Cr/SiO	99.95%
B	99.9% 99.9999%	CdO	99.99%	Cu	99.99% 99.999%
B ₂ O ₃	99.90%	CdS	99.99% 99.999%	Cu ₂ O CuO	99.90%
B ₄ C	99.50%	CdSe	99.99%	Cu ₂ S CuS	99.99%
Ba _x Sr _{1-x} TiO ₃	99.90%	CdTe	99.99% 99.999%	CuSe Cu ₂ Se	99.99%
BaFe ₁₂ O ₁₉	99.90%	CeF ₃	99.99%	Cu ₂ ZnSnS ₄	99.99%
BaO	99.90%	CoFe	99.95%	CuAlO ₂	99.90%

Formula	Purity	Formula	Purity	Formula	Purity
DyF ₃	99.99%	Gd ₂ O ₃	99.99%	LiCoO ₂	99.90%
DyFeO ₃	99.90%	Ge	99.999%	LiF	99.90%
Dy ₂ O ₃	99.99%	GeO ₂	99.99%	LiFePO ₄	99.90%
Er ₂ O ₃	99.99%	GeTe	99.99% 99.999%	LiMn ₂ O ₄	99.90%
ErF ₃	99.99%	Hf	99.95%	LiNbO ₃	99.99%
Eu ₂ O ₃	99.99%	HfC	99.90%	Mg	99.99%
EuF ₃	99.99%	HfSi	99.90%	MgAl ₂ O ₄	99.99%
Fe	99.9% 99.99%	In ₂ O ₃	99.99%	Mn	99.99%
Fe ₂ O ₃ Fe ₃ O ₄	99.90%	In ₂ O ₃ /Ga ₂ O ₃ / ZnO	99.99%	MnO MnO ₂	99.99%
FeCrAl	99.90%	In ₂ O ₃ /ZnO	99.99%	Mo	99.99%
FeMn	99.90%	InSb	99.99%	Mo ₂ C	99.99%
FePt	99.90%	In ₂ Se ₃	99.99%	MoO ₃	99.99%
FeS	99.90%	LaB ₆	99.90%	MoS ₂	99.99%
FeSi ₂	99.90%	LaMnO ₃	99.90%	MoSi ₂	99.99%
FeZr	99.90%	LaNiO ₃	99.90%	NaF	99.99%
Ga ₂ O ₃	99.99%	LaxSryMnO ₃	99.90%	NbC	99.50%
GaSb	99.99%	Li ₃ PO ₄	99.90%	NbN	99.50%

Formula	Purity	Formula	Purity	Formula	Purity
Ni	99.90%	SrTiO ₃	99.99%	VO ₂	99.90%
NiFe ₂ O ₄	99.90%	Ta	99.99%	VSi ₂	99.90%
Ni/Fe	99.90%	TaC	99.50%	WC	99.50%
NiO	99.90%	TaN	99.99%	WO ₃	99.90%
NiSi ₂	99.90%	TaSi ₂	99.50%	WS ₂	99.90%
PbS	99.90%	Te	99.99%	WSi ₂	99.90%
PbTe	99.99%	TeO ₂	99.99%	WTi	99.90%
PbTiO ₃	99.90%	Ta	99.99%	Y ₃ Fe ₅ O ₁₂	99.90%
PbZr _{0.52} Ti _{0.48} O ₃	99.90%	TaC	99.50%	YSZ	99.90%
Sb ₂ Te ₃	99.99%	TaN	99.99%	ZnO	99.99%
Sc ₂ O ₃	99.99%	TaSi ₂	99.50%	ZnO+Al ₂ O ₃	99.99%
Si ₃ N ₄	99.50%	Te	99.99%	ZnTe	99.99%
SiC	99.50%	TeO ₂	99.99%	ZrB ₂	99.50%
SnO	99.95%	TiB ₂	99.50%	ZrC	99.50%
SnO ₂	99.99%	TiC	99.50%	ZrN	99.50%
SnS	99.99%	TiN	99.50%		
SnS ₂	99.99%	V ₂ O ₅	99.90%		

• Evaporation Materials •

Formula	Typical Purity	Refractive Index (nd)	Transmission Range	Evaporation Temperature
Al ₂ O ₃	99.99%	1.64	200-5000nm	2000-2200°C
CeO ₂	99.99%	2.35	400- 16000nm	1950°C
HfO ₂	99.99%(Zr 2%) (Zr≤0.5%)	1.95-2.0	220-5000nm	2500°C
MgO	99.99%	1.7	200-8000nm	2000°C
SiO ₂	99.99% 99.999%	1.45	200-2000nm	1600-2500°C
SiO	99.9% 99.99%	1.85	500-8000nm	1200-1600°C
Ta ₂ O ₅	99.99%	2.1	400-7000nm	1950°C
Nb ₂ O ₃ NbO ₂	99.99%	2.24	400-7000nm	1800°C
TiO	99.90%	2.4	400-1200nm	1850°C
TiO ₂	99.9% 99.99%	2.35	400-1200nm	2200°C
Ti ₂ O ₃	99.90%	2.1	400-7000nm	1800°C
Ti ₃ O ₅	99.90%	2.35	400-7000nm	2000°C
Y ₂ O ₃	99.99%	1.75	400-8000nm	2500°C
Yb ₂ O ₃	99.99%	1.93	400-8000nm	2500°C
ZrO ₂ ZrO	99.9% 99.99%	2.05	250-7000nm	2500°C
In ₂ O ₃ +SnO ₂	99.99%	2	400-1100nm	1450°C
ZrO ₂ +Y ₂ O ₃	99.99%	1.9	250-7000nm	2500-2600°C
ZrO ₂ +TiO ₂	99.99%	2.1	400-7000nm	2300°C
TiO ₂ +Ta ₂ O ₃	99.9% 99.99%	2.25-2.3	400-7000nm	2300-2500°C
TiO ₂ +Nb ₂ O ₃	99.99%	2.2-2.3	400-7000nm	2300-2500°C
ZrO ₂ +Al ₂ O ₃	99.99%	1.7	250-7000nm	2400-2550°C

• Evaporation Materials •

Formula	Typctal Purity	Refractive Index (nd)	Transmission Range	Evaporation Temperature
La ₂ O ₃ +TiO ₂	99.99%	2	400-7000nm	2100-2200°C
Al ₂ O ₃ +La ₂ O ₃	99.99%	1.65	400-7000nm	2100-2200°C
BaF ₂	99.90%	1.4	220- 15000nm	1280°C
LaF ₃	99.99%	1.58	220- 14000nm	1450°C
PrF ₃	99.90%	1.34	350- 16000nm	1350°C
YbF ₃	99.99%	1.52	200- 12000nm	1200-1300°C
YF ₃	99.99%	1.5	200- 12000nm	1200-1300°C
MgF ₂	99.99%	1.38	153-7000nm	1300-1600°C
YF ₃ +BaF ₂	99.90%	1.35	400- 15000nm	1290°C
YF ₃ +CaF ₂	99.90%	1.35	400- 15000nm	~1290°C
Na ₃ AlF ₆	99.90%	1.35	300-9000nm	900-1200°C
Na ₅ Al ₃ F ₁₄	99.90%	1.33	300-9000nm	1130-1170°C
ZnS	99.99%	2.4	400-1400nm	1100°C
ZnSe	99.99%	2.6	500-2000nm	~1000°C
Au	99.9% 99.999%	N.A.	N.A.	1132 1282°C
Ag	99.99%	N.A.	N.A.	1105°C
Al	99.9% 99.999%	N.A.	N.A.	1010 1280°C
Pt	99.95% 99.99%	N.A.	N.A.	1742-2020°C
Hf	99.95%	N.A.	N.A.	8090°C
Zr	99.7% 99.9%	N.A.	N.A.	2260°C
Ti	99.7% 99.99%	N.A.	N.A.	1453°C

monocrystal substrate

New Crystal

	DyScO ₃	GdScO ₃	PrScO ₃	NdScO ₃
	MnO	CeO ₂	Cu ₂ O	Fe ₂ O ₄
	SnO ₂	Fe ₂ O ₃	ZnO/Al ₂ O ₃	
superconducting thin film				
	SrTiO ₃	LaAlO ₃	YSZ	MgO
	NdGaO ₃	KTaO ₃	SrLaAlO ₄	
Functional epitaxial thin films				
	SiO ₂ + Si	GaN on Sapphire wafer	P/Ti/SiO ₂ /Si wafer	
magnet ferroelectric thin film substrate				
	GGG substrate	Nb:SrTiO ₃ substrate	Fe:SrTiO ₃ substrate	PMN-PT substrate
Photo Transistor substrate				
	TiO ₂ Rutile substrate	SiO ₂ quartz monocrystal substrate	quartz glass substrate	YAlO ₃ substrate
	YAG substrate	LiNbO ₃ substrate	LiTaO ₃ substrate	
semiconducting crystal substrate				
	SOI Si+SiO ₂ +Si	Ge substrate	Si substrate	InP substrate
	InAs substrate	InSb substrate		
fluo-chloride crystal substrate				
	MgF ₂ substrate	CaF ₂ substrate	BaF ₂ substrate	LiF substrate
	KCl substrate	NaCl substrate	KBr substrate	
III-V crystal substrate				
	Sapphire wafer	GaN monocrystal substrate	LiAlO ₂ substrate	MgAl ₂ O ₄ substrate
II-VI crystal substrate				
	ZnO high resistivity substrate	ZnO low resistivity substrate	Ga:ZnO substrate	SiC substrate
ceramic substrate				
	Al ₂ O ₃ 96% substrate	AlN ceramic substrate	YSZ ceramicsubstrate	
Other materials				
	Cu metal monocrystalsubstrate	Al metal monocrystalsubstrate	Mg metal monocrystalsubstrate	KTa _(1-x) Nb _x O ₃
	K9 glass substrate	Sapphire Tube	Ruby Tube	